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| FORM: PTO-1449 (REV: 7-80) | U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE | Atty Docket No: 2001-0827.01 | Serial No: |
| INFORMATION DISCLOSURE STATEMENT BY APPLICANT (37 CFR 1.98(b)) | | Applicant: Christopher W. Hill | |
| | | Filing Date: May 19, 2004 | Group: |
| (use several sheets if necessary) | | | |

U.S. PATENT DOCUMENTS

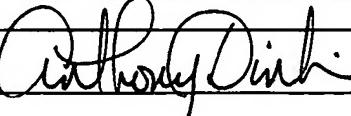
| Examiner Initial | Document Number | Date | Name | Class | Subclass |
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| AA | | | | | |
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FOREIGN PATENT DOCUMENTS

| Examiner Initial | Document Number | Date | Country | Class | Subclass | Translation Yes | Translation No |
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| AO | | | | | | <input type="checkbox"/> | <input type="checkbox"/> |
| AP | | | | | | <input type="checkbox"/> | <input type="checkbox"/> |
| AQ | | | | | | <input type="checkbox"/> | <input type="checkbox"/> |

OTHER ART (including author, title, date, pertinent pages, etc.)

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|---|----|--|---|
|  | AR | | "Synthese and characterization of aerosol silicon nanocrystal nonvolatile floating-gate memory device", M.L. Ostraat et al., Applied Physics Letters, Volume 79, Number 3, July 16, 2001, pages 433-435. |
|  | AS | | "Ultraclean Two-Stage Aerosol Reactor for Production of Oxide-Passivated Silicon Nanoparticles for Novel Memory Devices", Michele L. Ostraat et al., Journal of The Electrochemical Society, 148 (5), Pages G265-G270 |

Examiner:  Date Considered: **3/15/05**

EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication with applicant.